

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	"20020025408"	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 16:07
L2	1628	((977/887) or (264/293)).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 16:43
S1	20854	(nanoimprint\$4 step near3 flash near3 \$5imprint\$4) and (photoresist resist) with temperature\$2	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 12:51
S2	164	(nanoimprint\$4 step near3 flash near3 \$5imprint\$4) and (photoresist resist) with temperature\$2	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 12:52
S3	126	(nanoimprint\$4 step near3 flash near3 \$5imprint\$4) and (photoresist resist) with heat\$4	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:05
S4	28	(step near3 flash near3 \$5imprint\$4) and (photoresist resist) with heat\$4	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:05
S5	10	(step near3 flash near3 \$5imprint\$4) and (photoresist resist) same heat\$4 with (uv "u.v." ultraviolet)	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:06
S6	2201	(photoresist resist) same heat\$4 with (uv "u.v." ultraviolet)	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:07
S7	166	(photoresist resist) same heat\$4 with flow \$4 same (uv "u.v." ultraviolet)	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:07

S8	1019	(photoresist resist) same (bake baking baked) with during with (exposing exposed exposure expose)	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:11
S9	51	(photoresist resist) same (bake baking baked) with during with (exposing exposed exposure expose) with (uv "u.v." ultraviolet)	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:11
S10	208	(photoresist resist) same (bake baking baked heat\$4) same (uv "u.v." ultraviolet) and contact adj mask \$2	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:17
S11	96	(photoresist resist) same (heat\$4) same (uv "u.v." ultraviolet) and contact adj mask \$2	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:19
S12	29	(photoresist resist) same (heat\$4) same (uv "u.v." ultraviolet) same contact adj mask \$2	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:19
S13	5	(photoresist resist) same (heat\$4) with contact adj mask\$2	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:20
S14	1	10/659006	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:32
S15	49	(bailey and choi).in.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:35
S16	27	(sfil step near3 flash\$4 near3 \$5imprint) and (photoresist resist) with heat\$4	US-PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:38

S17	9	10/081199	US- PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 13:42
S18	288	nanoimprint\$4 same (uv ultraviolet "u.v.")	US- PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 14:16
S19	940	nanoimprint\$4 and (uv ultraviolet "u.v.")	US- PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 14:17
S20	1769	imprint adj lithography and (uv ultraviolet "u. v.")	US- PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 14:19
S21	236	imprint adj lithography with (uv ultraviolet "u. v.")	US- PGPUB; USPAT; USOCR	OR	OFF	2009/01/18 14:19

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